

## Method and apparatus for conditioning a polishing pad

**Publication number:** TW471992B

**Publication date:** 2002-01-11

**Inventor:** FINKELMAN ALEX (US)

**Applicant:** LAM RES CORP (US)

**Classification:**

- **International:** B24B21/04; B24B37/04; B24B53/10; B24B21/04;  
B24B37/04; B24B53/00; (IPC1-7): B24B37/04;  
B24B7/24; H01L21/304

- **European:** B24B21/04; B24B37/04; B24B53/10

**Application number:** TW20000128328 20010301

**Priority number(s):** US19990475518 19991230

**Also published as:**



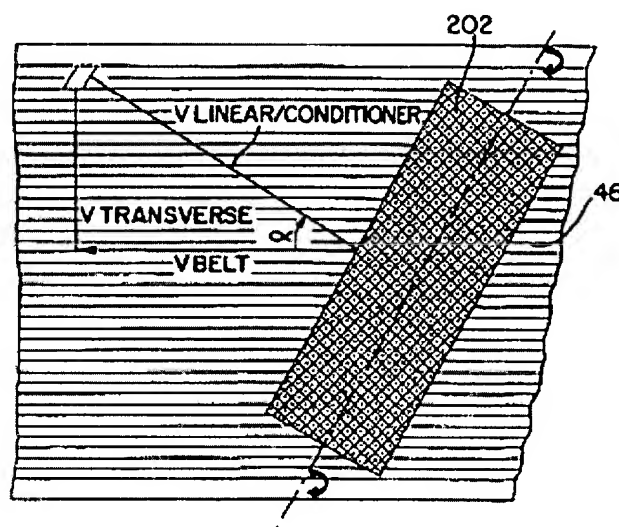
WO0149453 (A1)

US6306019 (B1)

[Report a data error here](#)

### Abstract of TW471992B

A method and apparatus for conditioning a polishing pad is described. The method includes steps of moving a cylindrical roller having an abrasive substance affixed to it against a moving polishing pad. The roller may be actively rotated or reciprocated at variable rates, while maintaining a pressure against the polishing pad. The apparatus includes a cylindrical roller to one another or more pressure application devices mechanically connected to the roller.



Data supplied from the esp@cenet database - Worldwide